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## (54) METHOD FOR PROCESSING SURFACE OF SUBSTRATE

(57)Abstract:

PROBLEM TO BE SOLVED: To provide such a cleaning method that satisfies three requirements, i.e., (1) no corroding of transition metal or transition metal compound and barrier metal, (2) superior removal of particle contamination on the surface of a substrate, and (3) superior removal of metallic contamination on the surface thereof, during cleaning of the substrate which has a transition metal or a transition metal compound on its surface.

SOLUTION: This method uses a surface processing agent which contains an organic alkaline and a complexing agent, and further a surfactant, and it is used to clean a substrate having a transition metal or a transition metal compound on its surface.

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